

Title (en)
CHEMICAL-MECHANICAL POLISHING COMPOSITIONS COMPRISING ONE OR MORE POLYMERS SELECTED FROM THE GROUP
CONSISTING OF N-VINYL-HOMOPOLYMERS AND N-VINYL COPOLYMERS

Title (de)
CHEMISCH-MECHANISCHE POLIERZUSAMMENSETZUNGEN MIT EINEM ODER MEHREREN POLYMEREN AUS DER GRUPPE AUS N-
VINYL-HOMOPOLYMEREN UND N-VINYL-COPOLYMEREN

Title (fr)
COMPOSITIONS DE POLISSAGE MÉCANO-CHIMIQUE COMPRENANT UN OU PLUSIEURS POLYMÈRES CHOISIS DANS LE GROUPE
CONSTITUÉ PAR LES HOMOPOLYMÈRES ET LES COPOLYMÈRES DE N-VINYLE

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Application
EP 14797029 A 20140505

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Abstract (en)
[origin: WO2014184702A2] Described is a chemical-mechanical polishing (CMP) composition comprising the following components: (A) surface modified silica particles having a negative zeta potential of -15 mV or below at a pH in the range of from 2 to 6 (B) one or more polymers selected from the group consisting of N-vinyl-homopolymers and N- vinyl copolymers (C) water (D) optionally one or more further constituents, wherein the pH of the composition is in the range of from 2 to 6.

IPC 8 full level
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CPC (source: EP US)
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